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See also Halstead-Reitan Test - another test of organic functions, composed by Reitan References External links Halstead-Reitan Test at Neurocomputational Research Group at the University of Texas at Austin Category:Neuropsychological tests Category:Educational psychology Category:Psychological testing1. Field of the Invention The present invention relates to a novel resist composition comprising a resin having a group capable of reacting with an acid (which may be hereinafter referred to as an “acid-decomposable group”) and a quinone-base photo-sensitizer which generates an acid upon irradiation with light. This invention also relates to a novel pattern forming process which comprises forming a patterned resist layer on a substrate through a dry-etching treatment, transferring the pattern formed to a substrate through a dry-etching treatment or a heat treatment using the resist layer as a mask, and thereafter developing the patterned resist layer by treatment with a developer. This invention also relates to a novel pattern forming process which comprises forming a patterned resist layer on a substrate through a dry-etching treatment, transferring the pattern formed to a substrate through a dry-etching treatment or a heat treatment using the resist layer as a mask, and thereafter developing the patterned resist layer by treatment with a developer and, after that, removing the substrate with the resist layer left thereon using the resist layer as a mask. 2. Description of the Related Art In the process of fabricating a semiconductor integrated circuit, a patterned resist layer is formed on a semiconductor substrate by a lithographic technique to use the resist layer as a mask to subject the semiconductor substrate to an etching treatment. The process of forming a resist pattern on a substrate through such a lithographic technique is hereinafter referred to as “lithographic process”. The substrate is generally subjected to a series of treatments such as resist-pattern forming, etching, cleaning and drying. The series of treatments must be carried out in a clean room. In this regard, a resist material capable of forming a high-resolution pattern is a very important material. Also, a resist material for a positive tone which undergoes no change in solubility between exposed and unexposed areas, and a resist material for a negative tone which undergoes a change in solubility between exposed and unexposed areas, are the resist materials of choice in current 54b84cb42d

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